Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	2503	427/248.1.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
S3	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
S4	934	427/255.7.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
S5	232	S2 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:14
S6	25	S3 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:36
S7	45	S4 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:53
S11	143	chang-mei.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:50
S12	158	chen-ling.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:52

S14	157	bis(allyl)palladium or bis(2-methylallyl)palladium or (cyclopentadienyl)(allyl)palladium or trimethyl(cyclopentadienyl)platinum or	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14	1 :10	
		trimethyl(methylcyclopentadienyl)pl atinum or (cyclopentadienyl)(allyl)platinum or dimethyl(cyclooctadiene)platinum						
4		or methyl(carbonyl)cyclopentadienylpl atinum or trimethyl(acetylacetonato)platinum						
		or bis(acteylactonato)platinum or (cyclopentadienyl)(cyclohexadienyl) cobalt or						.
,		(cyclobutadienyl)(cyclopentadienyl) cobalt or bis(cyclopentadienyl)cobalt or				·	·	
		bis(methylcyclopentadienyl)cobalt or cyclopentadenyl(1, 3-hexadienyl)cobalt or	-	· •				
		(cyclopentadienyl)(5-methylcyclope ntadienyl)cobalt or bis(ethylene)(pentamethylcyclopent						
		adienyl)cobalt or bis(methylcyclopentadienyl)nickel or bis(propylene)rhodium or bis(carbonyl)(cyclopentadienyl)rhodi						
		um or bis(carbonyl)(methylcyclopentadien yl)rhodium or					,	
	,	bis(carbonyl)(ehtylcyclopentadienyl) rhodium or (bis(allyl) palladium) or (bis(2-methylallyl) palladium) or ((cyclopentadienyl)(allyl) palladium) or trimethyl(cyclopentadienyl)				· .		
		platinum or trimethyl(methylcyclopentadienyl) platinum or (cyclopentadienyl)(allyl) platinum or						
		dimethyl(cyclooctadiene) platinum or methyl(carbonyl)cyclopentadienyl platinum or trimethyl(acetylacetonato) platinum						
		or bis(acteylactonato) platinum or (cyclopentadienyl)(cyclohexadienyl) cobalt or						
		(cyclobutadienyl)(cyclopentadienyl) cobalt or bis(cyclopentadienyl) cobalt or					·	
		bis(methylcyclopentadienyl) cobalt or cyclopentadenyl(1,3-hexadienyl) cobalt or (cyclopentadienyl)(5-methylcyclope				•		
	06 1:06:44 PM ments and Set	ntadienyl) cobalt or	spaces\1081123	0.wsp	<u> </u>	F	Page 2	
1	ļ [*]	his/methylovolonentadienyl) nickel	·			1		

S15	28	S14 and (silane or disilane or dimethylsilane or methyl silane or methylsilane or ethylsilane or ethylsilane or borane or diboran or triborane or tetraborane or pentaborane or hexaborane or heptaborane or octaborane of nanoborane or decaborane or "sih. sub.4" or "sic.sub.2h.sub.4" or "sic. sub.2.sub.8" or "sich.sub.6" or "sic. sub.2h.sub.8" or "bh.sub.3" or "b. sub.2h.sub.6" or "b.sub.3h.sub.9" or "b.sub.4h.sub.12" or "b.sub.5h. sub.15" or "b.sub.6h.sub.18" or "b. sub.7h.sub.21" or "b.sub.8h.sub.24" or "b.sub.9h.sub.27" or "b.sub.10h.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:22
S20	113597	sub.30") (palladium or pd or platinum or pt or cobalt or co or nickel or ni or rhodium or rh) and (silane or disilane or dimethylsilane or methyl silane or methylsilane or ethylsilane or ethylsilane or ethylsilane or ethylsilane or triborane or borane or diboran or triborane or tetraborane or pentaborane or hexaborane or heptaborane or octaborane or heptaborane or decaborane or "sih. sub.4" or "si.sub.2h.sub.4" or "sic. sub.2.sub.8" or "sich.sub.6" or "sic. sub.2h.sub.8" or "bh.sub.3" or "b.sub.3h.sub.9" or "b.sub.4h.sub.12" or "b.sub.5h. sub.15" or "b.sub.6h.sub.18" or "b. sub.7h.sub.21" or "b.sub.8h.sub.24" or "b.sub.9h.sub.27" or "b.sub.10h. sub.30")	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:24
S21	1133	S20 and ((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:32
S33	2	("6527855").PN.	US-PGPUB;	OR	OFF	2006/09/20 08:03
	- W ₂		USPAT; DERWENT; IBM_TDB	10 miles		
S34	2503	427/248.1.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 08:03

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S35	232	S34 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 08:03
S37	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT;	OR	ON	2006/09/20 08:03
			IBM_TDB		產權的規	医生物性生态
S38	25	S37 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 08:03
S40	934	427/255.7.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 08:03
S41	45	S40 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 08:03
S42	2503	-427/248.1.ccls.	US-PGPUB;	OR	ON	2006/09/20 10:23
			USPAT; DERWENT; IBM_TDB			
S43	232	S42 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:28
S44	37	S43 and (ruthenium ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON.	2006/09/20 10:23
S45	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S46 S47	25	S45 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd))) S46 and (ruthenium ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON ON	2006/09/20 10:23
) T	7	370 dilu (Tuuleillulli Tu)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	OIN	2006/09/20 10:23

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S48	934	427/255.7.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S49	45	S48 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:23
S50	4	S49 and (ruthenium ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S51	554	((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd))) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 14:08
S54	10	S51 and (2, 4-dimethylpentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:23
S55	481	S51 and reduc\$4	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:36
S56	29	ganguli-seshadri.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:34
S57	15	maity-nirmalya.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:34
S58	5	("20030037802" "5372849" "6003526" "6074945" "6537461").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/09/20 10:48
S59	554	((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd))) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:23
S60 .	10	S59 and (\$10methylpentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:24

S61	113	S59 and (\$15pentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:25
S62	13	S59 and (expanding with channel)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 14:09
S63	316	S59 and (chamber or apparatus)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 14:10
S64	4	shah-kavita.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:16
S65	715	427/255.28.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:16
S66	20	S65 and (atomic layer deposition or ald) and (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON.	2006/09/21 08:29
S67	558	(atomic layer deposition or ald) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:30
S68	473	S67 and (barrier layer or tantalum or tantalum nitride or tantalum silicon nitride or titanium or titanium nitride or titanium silicon nitride or tungsten or tungsten nitride)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON - :	2006/09/21 08:42
S69	111	S68 and resistivity	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:33
S70	20	S68 and sheet resistance	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON .	2006/09/21 08:44
S71	104	S67 and (barrier layer with copper)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:42

S72	421	S67 and (tantalum or tantalum nitride or tantalum silicon nitride or titanium or titanium nitride or titanium silicon nitride or tungsten or tungsten nitride)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:42
S73	22	S67 and sheet resistance	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ		2006/09/21 08:44